



Legionella Growth Supplement (BCYE)

FD142

A chemical enrichment supplement recommended for enhancing growth of *Legionella* species.

Composition

Per vial sufficient for 440 ml medium

Ingredients	Concentration
ACES buffer/ Potassium hydroxide	5g
Ferric pyrophosphate, soluble	0.125g
L-cysteine hydrochloride	0.20g
alpha-Ketoglutarate	0.50g
Distilled water	50 ml

Directions:

Warm up the refrigerated supplement to 45-50°C, shake well to form uniform suspension. Avoid frothing. Aseptically add to 440 ml sterile, molten, cooled (45-50°C) Legionella Agar Base [M809A](#) . If desired aseptically add rehydrated contents of 1 vial of Legionella (GVPC) Selective Supplement [FD143](#) . Mix well and pour into sterile petri plates. The final pH of the medium will be 6.9 ± 0.2 . In case of non incorporation of Legionella (GVPC) Selective Supplement [FD143](#) , add aseptically 10 ml sterile distilled water to bring the total volume to 500 ml medium.

Note:

If the 2 to 8°C stored vial on opening and exposure to air for longer time shows some precipitate, please shake the vial to evenly disperse the contents before adding to medium.

Storage and Shelf Life

Store at 2-8°C. Use before the expiry date on the label.

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Disclaimer :

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